

Subst. Form PTO-1449

INFORMATION DISCLOSURE CITATION  
IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)

SAM-0564

Application Number

Not yet assigned

Applicant

Jae-Yoon Yoo, *et al.*

Filing Date

Herewith

Group Art Unit

Not yet assigned

## U. S. Patent Documents

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

## FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
	AL							
	AM							
	AN							
	AO							
	AP							
	AQ							

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

WLL	AR	Tavel, B., <i>et al.</i> , "Totally Silicided (CoSi <sub>2</sub> ) Polysilicon: a novel approach to very low-resistive gate (~2Ω/□) without metal CMP nor etching." <i>IEDM 2001</i> , p. 825-828, December 2001
	AS	
	AT	

EXAMINER

*WLL*

DATE CONSIDERED

5/13/2005

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy with next communication to applicant.